



The Phase-2 ATLAS ITk Pixel Upgrade

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On behalf of the ATLAS Collaboration



TIPP, 22-26 May 2017, Bejiing, China



- Schedule of the HL-LHC
- The current Inner Detector and the ATLAS ITk Pixel upgrade
- R&D On Pixel Mechanics and Services
- The RD53 Collaboration
- R&D on pixel sensors and modules:
 - Bump-Bonding
 - 3D sensors
 - Planar sensors
 - An alternative option : CMOS



Schedule







The LHC will become the High-Luminosity-LHC (HL-LHC), to produce more than 3000 fb⁻¹ of integrated luminosity in 2035.

Higher integrated luminosity \rightarrow benefits precision measurements and studies of rare processes.



ATLAS Inner detector



HL-LHC scenario implies significant changes that affects the Inner detector w.r.t the current design:

- Peak luminosity: 5-7 x 10³⁴ cm⁻² s⁻¹ ~ x 5-7
- Average pile-up: up to $<\mu> \sim 200 \sim x 8$
- Integrated luminosity: 3000 fb⁻¹ $\sim x \ 10$
- required radiation hardness: $2x10^{16} n_{eq}/cm^2 \times 20$

Same or better performance are expected from the Inner Detector in Phase-II, in order to achieve this goal, several aspects are considered :

- Higher data rate capabilities for the sensor readout and stave services
- Smaller pixel segmentation to reduce misidentification and provide better tracking in dense environment
- Increased radiation hardness of the sensors w.r.t. to current technology
- Increased tolerance to SEU and TID for the readout electronics

ATLAS ITk will implement an all Silicon tracker :

- 65nm readout ASIC with 5Gbps maximum data rate (RD53)
- Radiation hardened pixel sensors in 3D and planar technology with small pixels
- New mechanics layout to increase Eta coverage and minimize material budget and optimize sensor cooling power

The layout of the ITk Pixel detector is currently under study by the Layout Task force to identify the final layout to be implemented among the one under study by the community, with different barrel and disk geometry and different Eta coverage.

See : Design of the new ATLAS Inner Tracker for the High Luminosity LHC, Jike Wang

Inclined layout

- Sensors along the barrel stave are inclined in order to be as perpendicular as possible to particles coming from the interaction point to reduce material budget
- Multiple space point per stave can be measured



<u>Common</u>

- Pixel volume up to 345 mm radius; then strip to the edge of the solenoid
- 5 Pixel Barrel and 4 (or 3) Rings layers, surface ~14 m²
- η coverage up to 4.0 (or 3.2) with at least 9 space points
- Pixel innermost detector replaceable.

Extended layout

- Long barrels covers a large eta region
- Large clusters at high-eta can be used to reconstruct tracklets



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LHC beam line





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The RD53 Collaboration



Technology	65nm CMOS
Pixel size	50x50 um²
Pixels	192x400 = 76800 (50% of production chip)
Detector capacitance	< 100fF (200fF for edge pixels)
Detector leakage	< 10nA (20nA for edge pixels)
Detection threshold	<600e-
In -time threshold	<1200e-
Noise hits	< 10 ⁻⁶
Hit rate	< 3GHz/cm ² (75 kHz avg. pixel hit rate)
Trigger rate	Max 1MHz
Digital buffer	12.5 us
Hit loss at max hit rate (in-pixel pile-up)	≤1%
Charge resolution	≥ 4 bits ToT (Time over Threshold)
Readout data rate	1-4 links @ 1.28Gbits/s = max 5.12 Gbits/s
Radiation tolerance	500Mrad at -15°C
SEU affecting whole chip	< 0.05 /hr/chip at 1.5GHz/cm ² particle flux
Power consumption at max hit/trigger rate	< 1W/cm ² including SLDO losses
Pixel analog/digital current	4uA/4uA
Temperature range	-40°C ÷ 40°C



The RD53 collaboration is developping the tools and designs needed to produce the next generation of pixel readout chips needed by <u>ATLAS</u> and <u>CMS</u> at the <u>HL-LHC</u>. The first prototype of a readout ASIC for HL-LHC will be submitted imminently

- Increased radiation hardness using 65nm technology
- First time using a fully synthetize digital part in a "sea of digital"
- Smallest pitch for hybrid LHC application so far , 50x50um², possibility for 25x100um²
- Shunt LDO implemented for compatibility with Serial Powering
- Highest data rate achievable per ASIC : 5Gbps



For ITK, the baseline is to rely on "traditional" bump-bonding, however new challenges emerge :

- 50x50 um² pixels, same pitch as before but 5 times higher density
- Larger ASIC wafer size (12")
- Larger sensor size (~ 4x4 cm)
- Thinner ASIC and Sensors (<150 um)

Work is ongoing to qualify bump-bonding for Itk pixel detector :

- Dummy wafers with **Daisy chain to test** the process at high-density, yield
- Stress-compensating layers or handling wafers to cope with thin assembly bow
- Evaluation of Bump-deposition vendors on 12"wafers
- Evaluation of UBM deposition by sensor vendors
- Evaluation of **in-house flip-chip** of modules for cost-saving
- Evaluation of alternate bonding methods (Indium, wafer to wafer bonding)







Pixel detectors : 3D Sensors

For the HL-LHC ITk Pixel detector upgrade, the **3D sensor technology**, originally developed and tested in the ATLAS IBL are the prime candidates for the inner layer where extreme radiation hardness is required to survive the dose foreseen.

The main challenges for this technology are the following :

- Smaller pixel needed (50x50 or 25x100 um²)
 - Column themselves are not efficient
- Thinner sensors considered (<150um)
 - Lower signal
 - Lower occupancy



Pixel detectors : 3D Sensors

Small pitch sensors were investigated in test beam before and after irradiation up to 1.4e16 n_{eq}/cm^2 , showing excellent detection efficiency. Power dissipation has been investigated for the new prototypes

In both case they perform similarly or better than the IBL generation equivalent

7781-W3-C1, 50x50 1E

781-W5-C2, 50x50 1E

Stand, FEI4 CNM34, 50x250 28

100

150

250

Reverse bias voltage (V)

300

200



6

8

50x50 1E. PS. 1ke, 7781-W4-C1

³ 10 12 14 Fluence [10¹⁵ n_{eo}/cm²]

Beam test measurements of irradiated 3D pixel sensors with 50x50 µm² pixel size, D.Vasquez, Trento 2017

Power dissipation (mW/cm



00

2



In bot

Pixel detectors : 3D Sensors

Small pitch sensors were investigated in test beam before and after irradiation up to 1.4e15 n_{eq}/cm^2 , showing excellent detection efficiency . Power



- dissipa for the • Pixel Detector Developments for Tracker Upgrades of the High Luminosity
 - LHC, Marco MESCHINI
- or bet equiva Joern LANGE



HV [V]

 $0 \times 50 \mu m^2$

14

HV (V)

16

Pixel detectors : Planar sensors

For the HL-LHC ITk Pixel detector upgrade , the **Planar sensor technology**, used in the outer layers of ATLAS Inner Detector and IBL are the prime candidates for the inner and outer layers.

The main challenges for this technology are the following :

- Low-Cost for the outer layer where a large amount of modules are needed
- Large area as Quad Assemblies are foreseen to be used in Itk
- Yield improvement needed
- Smaller pixel needed (50x50 or 25x100 um²)
 - Punch-Through structure, needed for improved yield is creating inefficiencies
 - Bias line steal signal after irradiation
- Thinner sensors considered (100-150um)
 - Lower signal
 - Lower occupancy
- New improved design



Pixel and Punch-Through structure design for $50x50\;\mu\text{m}^2\,\text{pixels}$



Pixel detectors : Planar sensors

CiS-4 n-in-p production



150 μm thick sensor, irradiated to $3 x 10^{15} \ n_{eq} / cm^2$



When assembling large area sensors, yield is an important parameter. The biasing structure on the sensors is important to identify good sensors before the bumpbonding This structure can lead to efficiency loss after irradiation and careful optimization of these structure is ongoing to minimize this

Latest results from development of n⁺-in-p planar pixel sensors and LGAD devices by KEK/HPK, Y. Unno, Trento 2017

FEI4 (250x50 um² pixels) was the only available ASIC for testing smaller pitch device, several structure were adapted to the FEI4 to allow small pitch studies and extrapolate to the performance expected with the RD53 ASIC

Thin planar pixel sensor productions at MPP for the ATLAS ITk, A Macchiolo, Trento 2017



Proton Irrad 3x1E15 1MeV n_{ea}/cm²



Pixel detectors : Planar sensors

0.9

0.8

0.7

CiS-4 n-in-p production

Side

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Proton Irrad 3x1E15 1MeV n_{ea}/cm²

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Planar and 3D technologies relies on Passive High-

Resistivity sensors

Specialty foundries -> small production capabilities

(6" wafers)

high-cost per unit

Small signal -> requires micro-soldering for DC coupling -> large cost

CMOS Technology present many advantages Large scale, low-cost production possible In-Pixel amplification and logic possible (Well insulation) Capacitive coupling to readout CMOS ASIC Eventually, possibility to integrate full electronics in-pixel









TJ standard

Particle hit

Pixel detectors : CMOS Sensors



Capacitively Coupled Pixel Detectors:
From design simulations to test beam,
Mateus Vicente

p" epitaxial layer

p substrate

D. Kim et al., JINST 11 C02042, 2016

ATLAS Perspectives and Conclusion

ATLAS Itk Pixel project propose an ambitious upgrade of the current ATLAS Inner Detector and is moving towards the TDR at the end of 2017

- Peak luminosity: 5-7 x 10^{34} cm⁻² s⁻¹ ~ x 5-7
- Average pile-up: up to $\langle \mu \rangle \sim 200 \sim x 8$
- Integrated luminosity: more than 3000 fb⁻¹ \sim x 10
- Requested radiation hardness: 2x10¹⁶ n_{eq}/cm² x 20

All system aspects are being addressed to cope with the new conditions and deliver an excellent Pixel detector for the Phase II of HL-LHC

- Mechanics and services are being optimized to offer better η coverage, lower material budget and more space points per track
- A new Readout ASIC is being developped to cope with the increased data rate, smaller pixel pitch and higher radiation dose
- Multiple sensor technologies are being studied to cope with the conditions at the different radii of the ITk Pixel detector
- Cost reduction strategies are being investigated for interconnect, sensor technologies and assembly process to cope with the large scale production needed for this project

Thank you for your attention! 感谢您的关注

backup

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Forward Region

1400 ATLAS ITk Simulation

STEP1 Layout concept: Fully Inclined 4.0

1000

1500

2500

3000

R [mm]

1200

The forward region will be consist of four layers of ring located a different radii and z

- Compared to disk, ring offer more flexibility for maintaining hermeticity
- Each ring consists of a carbon core containing cooling and electrical services.
- Rings are built out of two half-rings, for ease of construction
- Modules are mounted on both sides of each ring to allow overlap



z [mm]TIPP, 22-26 May 20

- **Demonstrator program** : Evaluation and validation of a complete SLIM Longeron
 - mechanical integration, DCS + serial powering, multi-module readout, electrical and thermal performance, system-test
- SLIM Layer 2+3 longeron (1.6 m)
 - 4 cooling lines:

.AS

- One cooling line equipped with electrical modules
- The rest with thermo-mechanical dummy modules (with heaters)
 - Dedicated stave-flexes for either electrical or dummy modules
- Serial powering scheme, stave-flex running inside longeron
- PSPP chips and DCS controller emulator (FPGA) at both ends
- Multiple readout systems
- CO₂ Cooling

Assembly jig design





Serial powering scheme



Cell integration





Data transmission scheme



DCS Chip testing f@serial powering



LFoundry 150 nm

ams 0.35 µm/180 nm



p-epi layer. Full CMOS electronics are possible in the sensor area.

6

- Metal layers
- Gate oxide 3 nm (good for radiation tolerance)
- **HR** $1k 8k \Omega \cdot cm$
- **HV** -6 V < HV < 0 V
- **Epi-layer** 18 40 μm thick
- Backside biasing Possible
- <u>Small n-well diode</u> → <u>low sensor capacitance</u> (~5 fF) → higher gain, better SNR, faster signal and potentially lower power consumption

CERN-TJ modified process:

- Normally, small electrodes produce weak fields under deep p-wells and signal collection after irradiation becomes difficult on edges (efficiency drop towards pixel edges)
- CERN-TJ → Add planar n-type layer to significantly <u>improve lateral</u> <u>depletion and charge collection after irradiation</u>. Implemented in Investigator test chip.

Prototypes:

- ALPIDE (ALICE upgrade chip), MISTRAL, ASTRAL, CHERWELL, Explorer, Investigator, MALTA, MonoPix



PWELL NWELL DEEP PWELL	NWELL DIODE	TRANSISTORS NMOS PMOS	
р	CER	N-TJ modified	
H. Perneg	ger, Trent	o Workshop, 2017	





PWELL	Fluence [n _{eq} /cm ²]	Average Hit Efficiency
	1.3·10 ¹⁴	98.1%
	5·10 ¹⁴	99.7%
CERN-13 modified Trento Workshop, 2017 MonoDix	1 · 10 ¹⁵	99.7%
TIPP, 22-26	5. <u>10¹⁵</u> May 2017, Bejiing, China	97.6% 24



ams 0.35 µm/180 nm



Prototypes:

- ams 0.35 μm → Initial R&D developments, H35CCPDv1-2, H35DEMO, HVStrip, CHESS1-2 (strips)



LFoundry 150 nm



Prototypes:

- CCPD LF (VA/VB), LF-CPIX Demo. (VA/VB), MonoPix Demo., COOL, LF ATLASPix, LFHVMAPS FEI3





N-well

deep N-well

TowerJazz 180 nm

Key features:

- Technology node 180 nm
- Deep p-well to isolate n-wells from - Wells p-epi layer. Full CMOS electronics are possible in the sensor area.
- Metal lavers
- 3 nm (good for radiation tolerance) - Gate oxide

6

- HR 1k – 8k Ω·cm
- -6V < HV < 0V- HV
- 18 40 um thick - Epi-laver
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p sub strate TJ standard Particle hit D. Kim et al., JINST 11 C02042, 2016



CERN-TJ modified

H. Perneager, Trento Workshop, 2017





ams 0.35 µm/180 nm



Prototypes:

- ams 0.35 μm → Initial R&D developments, H35CCPDv1-2, H35DEMO, HVStrip, CHESS1-2 (strips)



LFoundry 150 nm



Wells Deep p-well (PSUB) to isolate n-wells from deep n-well (collecting electrode). Full CMOS electronics are possible in the sensor area.

- Metal lavers 6
- HR $10 \Omega \cdot cm - \sim 4k \Omega \cdot cm$
- HV -120 V < HV < 0 V
- Depletion region ~170 µm thick @ -110 V
- Backside biasing Possible
- Stitching Possible

Prototypes:

- CCPD_LF (VA/VB), LF-CPIX Demo. (VA/VB), MonoPix Demo., COOL, LF_ATLASPix, LFHVMAPS_FEI3







p view of single pis

C_{PSUB_DNWELL} non-negligible

P-woll

P. Rymaszewski, JINST 11 C02045, 2016

esua deep P-well

N-well

deep N-well

\$r90 on \$0x50um pixel for modified process after peutrop irrediation 0.035 irradiated MPV = 18.937 +/- 0.122 mV 0.03 1e14 neg MPV = 19,499 +/- 0,147 mV 15 neg MPV = 15.904 +/- 0.124 mV 0.025 MPV = 19 mV pre-rad 16 mV after 1.0.1015 n_/cm 0.02 0.015 0.01 0.005 walleyngen ar allen 50

Signal [mV]





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PMOS NMOS TRANSISTOR, TRANSISTOR

n*

p epitaxial layer

p substrate

NWELL Spacing DIODE Spacing

diode

TJ standard

Deple

regio

Particle hit

[m

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20

0

-20

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